L Numbe			DB	Time stamp
1	16	UHV same susceptor	USPAT;	2003/04/04 10:02
			US-PGPUB;	
			EPO; JPO;	
	1		DERWENT;	
3	1	batch same susceptor and UHV	IBM_TDB	2002/04/04 20 20
	_	sacon same susceptor and one	USPAT;	2003/04/04 10:05
			US-PGPUB; EPO; JPO;	1
			DERWENT;	
	Ì		IBM TDB	
4	93	batch same susceptor and CVD	USPAT;	2003/04/04 10:06
			US-PGPUB;	2003/04/04 10:00
			EPO; JPO;	
			DERWENT;	
5			IBM_TDB	
5	9			2003/04/04 10:19
		CVD	US-PGPUB;	
			EPO; JPO;	
	İ		DERWENT;	
6	24	(planarty or planetary) same susceptor	IBM_TDB	
		'transit' of prometary) same susceptor	USPAT;	2003/04/04 11:41
			US-PGPUB; EPO; JPO;	
			DERWENT;	
			IBM TDB	
12	32	susceptor same (temperature or thermal)	USPAT;	2003/04/04 13:54
	}	near5 (control\$4 or monitor\$4) same	US-PGPUB;	2003/04/04 15.54
		(sensor or thermocouple) and cvd.ti.	EPO; JPO;	
			DERWENT;	
• •			IBM TDB	1
13	28	our / comporator or chermar/	USPĀT;	2003/04/04 13:56
		near5 (control\$4 or monitor\$4) same	US-PGPUB;	
		(sensor or thermocouple) same vacuum and	EPO; JPO;	ł
		cvd	DERWENT;	
14	5	suscenter same /temperature	IBM_TDB	
17	1	susceptor same (temperature or thermal) near5 (control\$4 or monitor\$4) same	USPAT;	2003/04/04 13:58
	ł	(sensor or thermocouple) same vacuum and	US-PGPUB; EPO; JPO;	
		cvd and batch	DERWENT;	
			IBM TDB	
18	1	planetary same susceptor and susceptor	USPAT;	2003/04/04 14:00
		same (sensor or thermocouple ) and cvd	US-PGPUB;	
		-	EPO; JPO;	
			DERWENT;	
2.7			IBM_TDB	
37	4	deep adj trench same CVD and @py<2001 and	USPAT;	2003/04/04 15:11
	1	UHV	US-PGPUB;	
			EPO; JPO;	
			DERWENT;	
38	2	deep adj trench same CVD same vacuum and	IBM_TDB USPAT;	2003/04/04 15:11
	-	epy<2001	US-PGPUB;	2003/04/04 15:11
			EPO; JPO;	
			DERWENT;	
			IBM TDB	
39	1	deep adj trench same CVD and @py<2001 and	USPAT;	2003/04/04 15:13
		117/\$4.ccls.	US-PGPUB;	
	]		EPO; JPO;	
			DERWENT;	
10			IBM_TDB	
10	83	deep adj trench same CVD and @py<2001 and	USPAT;	2003/04/04 15:26
		438/\$4.ccls.	US-PGPUB;	
		İ	EPO; JPO;	
	1		DERWENT;	
		· •	IBM TDB	
1	110	(ald or atomic add laws add damested)		2002/01/01 !
1	110	(ald or atomic adj layer adj deposit\$4)	USPĀT;	2003/04/04 15:28
1	110	(ald or atomic adj layer adj deposit\$4) same Si	USPĀT; US-PGPUB;	2003/04/04 15:28
1	110		USPĀT;	2003/04/04 15:28

42	2	(ald or atomic adj layer adj deposit\$4) same Si and UHV	USPAT; US-PGPUB;	2003/04/04 15:29
			EPO; JPO;	
			DERWENT; IBM TDB	
43	29	(ald or atomic adj layer adj deposit\$4 or	USPAT;	2003/04/04 15:32
		ale) and UHV	US-PGPUB;	
-			EPO; JPO;	
			DERWENT;	
73	10	ale and suntola.in.	IBM_TDB USPAT:	2003/04/04 15:42
			US-PGPUB;	2003/04/04 13:42
1			EPO; JPO;	
			DERWENT;	
74	3	(ald or atomic adj layer adj deposit\$4 or	IBM_TDB USPAT;	2003/04/04 15:33
	1	ale) same UHV	US-PGPUB;	2003/04/04 15:33
			EPO; JPO;	
			DERWENT;	
75	3	(ald or atomic adj layer adj epitax\$4 or	IBM_TDB	0000/04/04 45 05
		ale) same UHV	USPAT; US-PGPUB;	2003/04/04 15:37
			EPO; JPO;	
			DERWENT;	
76	458	(ald or atomic adj layer adj epitax\$4 or	IBM_TDB	
	150	ale) same vacuum	USPAT; US-PGPUB;	2003/04/04 15:37
ļ	1	, , , , , , , , , , , , , , , , , , , ,	EPO; JPO;	
			DERWENT;	
_	9	hans.in. and buschbeck.in.	IBM_TDB	
	,	nans.in. and buschbeck.in.	USPAT; US-PGPUB;	2003/04/02 15:28
	[		EPO; JPO;	
			DERWENT;	,
_		//////	IBM_TDB	
-	) 5	((UHV or ultra adj high adj vacuum) same (CVD or chemical adj vapor adj deposit\$4)	USPAT; US-PGPUB;	2003/03/25 13:08
		or UHV\$1CVD) same batch and (treat\$4 or	EPO; JPO;	i
		clean\$4) same vacuum	DERWENT;	
l _	,		IBM_TDB	
-	7	((UHV or ultra adj high adj vacuum) same (CVD or chemical adj vapor adj deposit\$4)	USPAT; US-PGPUB;	2003/03/25 13:09
		or UHV\$1CVD) same batch	EPO; JPO;	
			DERWENT;	
	1.0	(harden and the bottom of the bottom)	IBM_TDB	
-	10	(hydrogen or "h.sub.2") near4 plasma same clean\$4 same (ev)	USPAT; US-PGPUB;	2003/04/03 11:04
			EPO; JPO;	
			DERWENT;	
_	4	(hydrogen or the sub 2th)	IBM_TDB	0000/04/00 11 55
	4	(hydrogen or "h.sub.2") near4 plasma same (ev) same (wafer or substrate) same oxide	USPAT; US-PGPUB;	2003/04/03 11:07
		(11) Jame (11212 21 Substitute) Sume Oxide	EPO; JPO;	
			DERWENT;	
_	48	(hydrogon or "h ouh 2") massa alassa	IBM_TDB	2002/04/22 22 22
=	48	(hydrogen or "h.sub.2") near4 plasma same (ev) same (wafer or substrate)	USPAT; US-PGPUB;	2003/04/03 11:07
		(11) Same (naid) of Substitute/	EPO; JPO;	
			DERWENT;	
· _	21	(hydrogon or the sub 20)	IBM_TDB	2002/01/22 22 22
	21	(hydrogen or "h.sub.2") near4 plasma near20 (ev) same (clean\$4 or passivat\$4 or	USPAT; US-PGPUB;	2003/04/03 11:32
		oxide)	EPO; JPO;	1
	] ]		DERWENT;	
_	24	/hydrogen on the sub 200 4 1	IBM_TDB	
	24	<pre>(hydrogen or "h.sub.2") near4 plasma near10 energy same (clean\$4 or passivat\$4</pre>	USPAT; US-PGPUB;	2003/04/03 11:42
		or native adj oxide) same (wafer or	EPO; JPO;	
		substrate)	DERWENT;	
	L1		IBM_TDB	

-	8	to or all or acomic day layer ad	USPAT;	2003/04/03 13:25
		(epitax\$4 or deposit\$4)) same (UHV or	US-PGPUB;	
	1	ultra adj high adj vacuum)	EPO; JPO;	
	1		DERWENT;	
			IBM TDB	
-	78	(CVD or chemical adj vapor adj deposit\$4)	USPAT;	2003/04/03 14:28
		and vertical same horizontal same batch	US-PGPUB;	
ļ	1		EPO; JPO;	
			DERWENT;	}
			IBM TDB	
-	11	(UHV or ultra adj high adj vacuum near4	USPAT;	2003/04/03 15:06
		(CVD or chemical adj vapor adj deposit\$4))	US-PGPUB;	
		same vertical same horizontal	EPO; JPO;	i
	1		DERWENT;	
i			IBM TDB	
-	1	(UHV or ultra adj high adj vacuum near4	USPAT;	2003/04/03 14:40
		(CVD or chemical adj vapor adj deposit\$4))	US-PGPUB;	
		same vertical near5 reactor	EPO; JPO;	
	1		DERWENT;	
ļ			IBM TDB	
_	56	i (am ar arera aa) widu aal Aacaam Heald	USPAT;	2003/04/03 15:13
		(CVD or chemical adj vapor adj deposit\$4))	US-PGPUB;	
		and (vacuum near10 (furnace or heater))	EPO; JPO;	
			DERWENT;	
			IBM_TDB	
_	2	5755938.pn.	USPĀT;	2003/04/03 16:09
			US-PGPUB;	
			EPO; JPO;	
			DERWENT;	
			IBM_TDB	
_	85	temperature near10 control near10	USPĀT;	2003/04/04 10:00
		distribution same (reactor or chamber) and	US-PGPUB;	
		(CVD or chemical adj vapor adj deposition)	EPO; JPO;	
			DERWENT;	
			IBM TDB	